

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Hisaji OYAKE et al.

Application No.: New U.S. National Stage of
PCT/JP03/00020

Filed: July 7, 2004

Docket No.: 120321

For: METHOD OF MANUFACTURING STAMPER FOR MANUFACTURING
INFORMATION MEDIUM, STAMPER, AND PHOTORESIST MASTER

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

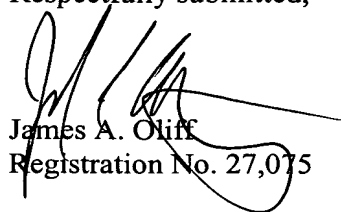
Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- ☒ 2. The references 1 and 4-12 were cited in a counterpart foreign application. An English language version of the foreign search report is attached for the Examiner's information.
- ☒ 3. English-language Abstracts of the non-English language references 1-12 are attached hereto.

10/500816
DT04 Rec'd PCT/PTO 07 JUL 2004

- ☒ 4. A computer-generated English translation of the following Japanese references have been obtained from the website of the Japanese Patent Office (<http://www.jpo.go.jp>), and are attached, but have not been reviewed for accuracy. See References 2 and 4-12.

Respectfully submitted,


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| Form PTO-1449 (REV. 8-83) | | US Dept. of Commerce PATENT & TRADEMARK OFFICE | | ATTY DOCKET NO. 120321 | | APPLICATION NO. New U.S. National Stage of PCT/IP03/00020 10/500816 | |
| INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) | | | | APPLICANTS Hisaji OYAKE et al. | | | |
| | | | | FILING DATE July 7, 2004 | | | |
| U.S. PATENT DOCUMENTS | | | | | | | |
| EXAMINER INITIAL | | DOCUMENT NUMBER | DATE | NAME | CLASS | SUB CLASS | |
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| FOREIGN PATENT DOCUMENTS | | | | | | | |
| | | DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUB CLASS | |
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| | 2 | JP A 9-292715 w/abstr. + trans. | 11/11/1997 | Japan | | | |
| | 3 | JP A 3-180476 w/abstr. | 08/06/1991 | Japan | | | |
| | 4 | JP A 7-147026 w/abstr. + trans. | 06/06/1995 | Japan | | | |
| | 5 | JP A 2001-344831 w/abstr. + trans. | 12/14/2001 | Japan | | | |
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| | 8 | JP A 6-215422 w/abstr. + trans. | 08/05/1994 | Japan | | | |
| | 9 | JP A 8-273219 w/abstr. + trans. | 10/18/1996 | Japan | | | |
| | 10 | JP A 5-214547 w/abstr. + trans. | 08/24/1993 | Japan | | | |
| | 11 | JP A 8-283950 w/abstr. + trans. | 10/29/1996 | Japan | | | |
| | 12 | JP A 9-109276 w/abstr. + trans. | 04/28/1997 | Japan | | | |
| OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.) | | | | | | | |
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| Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | | | | | |

Date: July 7, 2004